

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S69	10	liquid adj gallium with laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 12:18
S70	60	atomic adj clock with rubidium and laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:27
S71	2	atomic adj clock and rubidium with aluminum	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:27
S72	2	atomic adj clock and rubidium same aluminum	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:28
S73	12	rubidium with aluminum same laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:30
S74	2	("6265945"   "6570459").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 12:28
S75	59	(rb rubidium) with (aluminum al) with laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:34
S76	9	(rb rubidium) with (aluminum) with laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 12:35
S77	2	("6265945"   "6570459").PN.	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 12:52
S78	2	rubidium with (cap\$3) and passivat\$5	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 12:56
S79	36	gallium with tungsten with heat	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 12:57
S80	24	gallium with tungsten with laser	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 13:01
S81	15	alkali near3 vapor with atomic adj clock	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 13:16

S82	34	laser adj etch\$3 and reactive adj material	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:04
S83	27	(microelectronic MEMS) and laser and rubidium with aluminum	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 13:36
S84	106	(microelectronic MEMS) and laser and gallium with tungsten	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 13:38
S85	2	(microelectronic MEMS) and laser and liquid adj gallium with tungsten	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 13:55
S86	4	laser and liquid adj gallium with tungsten	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 13:55
S87	79	laser adj ablation and reactive adj material	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:04
S88	13	laser adj ablation and alkali near4 vapor	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:10
S89	52	427/96.2.ccls. and laser	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:30
S90	58	protective near3 (coat\$3 layer\$3) same rubidium	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:14
S91	25	("3300332").URPN.	USPAT	OR	ON	2005/07/25 14:41
S92	540	protective near3 (coat\$3 layer\$3) same gallium	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:47
S93	19	protective near3 (coat\$3 layer\$3) same gallium with tungsten	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:47
S94	40	protective near3 (coat\$3 layer\$3) same gallium same tungsten	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:41
S95	4	laser adj radiation with protective adj coat\$5	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 14:56
S96	5	laser adj radiation with remov\$4 adj polymer	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:01

S97	15	laser with transparent with enclosure with radiation	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 17:24
S98	1	laser adj irradiation with remov\$4 adj polymer	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:01
S99	50	MEMS with transparent with radiation	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:16
S100	0	MEMS with rubidium and transparent with radiation	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:15
S101	14	MEMS with rubidium	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 15:15
S102	37	atomic adj clock with rubidium and \$2radiation	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 15:20
S103	25	atomic adj clock with rubidium and \$2radiation and laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 15:23
S104	10	atomic adj clock and transparent with laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 15:33
S105	23	rubidium with (deposit\$3 coat\$3 film) and microelectronic	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 15:56
S106	1	rubidium with vaporize same laser	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/25 15:57
S107	25	("3300332").URPN.	USPAT	OR	ON	2005/07/25 16:39
S108	43	microelectronic and (rubidium lithium cesium) same protective adj (cover\$3 layer\$3 film cap\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:46
S109	44	reactive adj material with protective adj (cover\$3 layer\$3 film cap\$3)	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:57
S110	1	reactive adj material with protective adj (cover\$3 layer\$3 film cap\$3) with electronic	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:47
S111	0	427/226.ccls. and reactive adj material with microelectronic	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:58

S11 2	15	427/226.ccls. and reactive adj material	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 16:58
S11 3	13	427/226.ccls. and rubidium	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 17:24
S11 4	84	laser with transparent near3 enclosure	US-PGPUB; USPAT; USOCR	OR	ON	2005/07/25 17:28
S11 5	21	gallium with tungsten with reactive	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 12:53
S11 6	12	liquid adj gallium with tungsten	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:13
S11 7	18	(gallium) with (tungsten W) and "385"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:17
S11 8	247	(gallium) with (tungsten W) and "427"/\$.ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:39
S11 9	7	427/58,97.1,97.6,248.1,96.8.ccls. and mask with vapor and (rubidium gallium)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:42
S12 0	192	427/58,97.1,97.6,248.1,96.8.ccls. and (micro\$5electronic "MEMS") and vapor adj deposition	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:43
S12 1	2	427/58,97.1,97.6,248.1,96.8.ccls. and (micro\$5electronic "MEMS") and vapor adj deposition and rubidium	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:43
S12 2	38	427/58,97.1,97.6,248.1,96.8.ccls. and (micro\$5electronic "MEMS") and vapor adj deposition and gallium	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2005/07/27 13:43